

QUERY CONTROL FORM		RTIS USE ONLY	
Application No. <u>10074561</u>	Prepared by <u>PAP</u>	Tracking Number <u>05960924</u>	
Examiner-GAU <u>Smith-2877</u>	Date <u>7/26/04</u>	Week Date <u>6/7/04</u>	
	No. of queries <u>2</u>		

JACKET			
a. Serial No.	f. Foreign Priority	k. Print Claim(s)	p. PTO-1449
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other

SPECIFICATION	MESSAGE
a. Page Missing b. Text Continuity c. Holes through Data d. Other Missing Text e. Illegible Text f. Duplicate Text g. Brief Description h. Sequence Listing i. Appendix j. Amendments k. Other	<p>① There are two renumbered claim 14 (original claims 18, 22) on the Index of Claims. There is no claim 17.</p> <p>② PTO-1449: Please either initial or line through citation(s). Copy provided for reference.</p>
CLAIMS a. Claim(s) Missing b. Improper Dependency c. Duplicate Numbers d. Incorrect Numbering e. Index Disagrees f. Punctuation g. Amendments h. Bracketing i. Missing Text j. Duplicate Text k. Other	<p style="text-align: right;">Thank you</p> <p style="text-align: right;">initials PAP</p> <p>RESPONSE</p>
	initials

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Docket Number (Optional) TWI-30400	Application Number 10/074,561
	Applicant(s) Abdurrahman Sezginer et al.	
	Filing Date February 12, 2002	Group Art Unit 2877

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	AA	5,712,707	01/27/1998	Ausschnitt et al.	356	401	11/20/1995
	AB	5,795,687	08/18/1998	Yasuda	430	22	02/23/1996
	AC	5,805,290	09/08/1998	Ausschnitt et al.	356	401	05/02/1996
	AD	6,130,750	10/10/2000	Ausschnitt et al.	356	401	08/28/1997
	AE	6,458,605	10/01/2002	Stirton	438	7	06/28/2001
	AF	2003/0190793	10/09/2003	Brill et al.	438	401	09/20/2001

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AG	62157295	06/23/1987	Japan	H01L	21/30	Abstract	
	AH	0 192 656 B1	05/23/1990	EPO	G01B	11/06		
	AI	WO 00/72093 A1	11/30/2000	PCT	G03F	9/00		
	AJ	WO 02/25723 A2	03/28/2002	PCT	H01L	21/66		

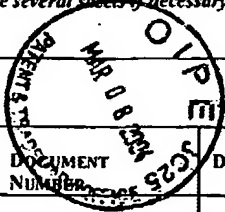
OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

	AK	C.C. Baum et al., "Scatterometry for Post-etch Polysilicon Gate Metrology", <i>Part of the SPIE Conference on Metrology, Inspection and Process Control for Microlithography XIII</i> , Santa Clara, CA, March 1999, SPIE Vol. 3677, pp. 148-158.
	AL	J. Bischoff et al., "Single feature metrology by means of light scatter analysis", <i>SPIE</i> , Vol. 3050 (1997), pp. 574-585.
	AM	J. Bischoff et al., "Diffraction analysis based characterization of very fine gratings", <i>SPIE</i> , Vol. 3099 (1997), pp. 212-222.
	AN	J. Bischoff et al., "New aspects of optical scatterometry applied to microtechnology", <i>SPIE</i> , Vol. 3215 (1997), pp. 144-155.
	AO	J. Bischoff et al., "Modeling of optical scatterometry with finite-number-of-periods gratings", <i>Part of the EUROPTO Conference on In-Line Characterization Techniques for Performance and Yield Enhancement in Microelectronic Manufacturing</i> , Edinburgh, Scotland, May 1999, SPIE Vol. 3743, pp. 41-48.
	AP	J. Bischoff et al., "Characterization of 3D resist patterns by means of optical scatterometry", <i>Part of the EUROPTO Conference on In-Line Characterization Techniques for Performance and Yield Enhancement in Microelectronic Manufacturing</i> , Edinburgh, Scotland, May 1999, SPIE Vol. 3743, pp. 49-60.
	AQ	J. Bischoff et al., "Light Diffraction Based Overlay Measurement", <i>Metrology, Inspection, and Process Control for Microlithography XV</i> , SPIE Vol. 4344 (2001), pp. 222-233.
	AR	T. Bosworth et al., "Critical-dimension and overlay metrology: a review", <i>Solid State Technology</i> , September 1995, pp. 119-123.
	AS	"Method for Measuring Semiconductor Lithographic Tool Focus and Exposure", <i>IBM Technical Disclosure Bulletin</i> , July 1987, pp. 516-518.
	AT	"Interferometric Method of Checking the Overlay Accuracy in Photolithographic Exposure Processes", <i>IBM Technical Disclosure Bulletin</i> , Vol. 32, No. 10B, March 1990, pp. 214-217.

Examiner	Date Considered
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

AU	"Phase-Sensitive Overlay Analysis Spectrometry", <i>IBM Technical Disclosure Bulletin</i> , Vol. 32, No. 10A, March 1990, pp. 170-174.
AV	"Interferometric Measurement System for Overlay Measurement in Lithographic Processes", <i>IBM Technical Disclosure Bulletin</i> , February 1994, pp. 535-536.
AW	"Interferometric Method of Checking the Overlay Accuracy in Photolitho Graphic Exposure Processes", <i>IBM Technical Disclosure Bulletin</i> , March 1990, pp. 214-217.
AX	P. Heimann, "The Color-Box alignment vernier: a sensitive lithographic alignment vernier read at low magnification", <i>Optical Engineering</i> , July 1990, Vol. 29, No. 7, pp. 828-836.
AY	"Layer Alignment/Overlay: Optical Diffraction", Nerac.com Retro Search, NERAC Inc., April 19, 2002, 93 pages in length.
AZ	"Lateral Shift: Optical Methods/Techniques", Nerac.com Retro Search, NERAC Inc., April 19, 2002, 90 pages in length.
BA	"Scatterometry and Overlay", Nerac.com Retro Search, NERAC Inc., April 19, 2002, 8 pages.
BB	N. Blayo et al., "Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features", <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599.
BC	S. Sohail et al., "Optical Scatterometry for Process Metrology", <i>SPIE Vol. CR 72</i> (1999), pp. 129-143.

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